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| IN THE UNITED STATES PATENT AND TRADEMARK OFFICE |                                      |          |  |
|--|--------------------------------------|----------|--|
| In Re Application of:                            |                                      |          |  |
|  | ;                                    | )        |  |
| Nozawa et al.                                    |                                      | )        | I hereby certify that this correspondence is being deposited           |
|  | ;                                    | )        | with the United States Postal Service as first class mail in an        |
| Serial No.: 10/667,823                           |                                      | ,<br>) . | envelope addressed to:   |
|  |                                      | <b>,</b> | Commissioner for Patents , P.Q. Box 1450, Alexandria, VA 22313-1450 on |
| Filed: Sen                                       | stember 22, 2003                     | ,        |  |
| Theu. Sep  | Memoer 22, 2003                      | ,        | Varuary 23 2006  |
| E DI   |                                      | ,        | ∫ (Date of Deposit)  |
| For: Phase Mask Shift Blank, Photo Mask Blank, ) |                                      | )        |  |
| And  | d Manufacturing Apparatus And Method | )        | Shannon Wallace  |
| Of Blanks  |                                      |          | Name of applicant, assignee, or Registered Rep.                        |
| Of Dialiks                                       |                                      | ,        | Shanni Willaro 1/23/06   |
|  |                                      | )        | Signature Date   |
| Examiner:  | Rodney Glenn McDonald                | )        |  |

Commissioner of Patents P. O. Box 1450 Alexandria, VA 22313-1450

1753

## **AMENDMENT (C) AFTER FINAL**

Dear Sir:

Art Unit:

In response to the Final Rejection of October 24, 2005, please enter the following amendment in the above-identified application: